

IN THE SPECIFICATION

1. Please amend the title of the invention as follows:

MASK FOR COLOR CATHODE RAY TUBE HAVING BENEFICIAL SLOT AND BRIDGE CONFIGURATIONS, MANUFACTURING METHOD THEREOF, AND EXPOSURE MASK FOR MANUFACTURING THE MASK

2. Please amend paragraph [0005] as follows:

[0005] A slot mask is designed to have the same curvature as a screen surface in consideration of landing of deflected electron beams. A mask as described above is obtained by forming a plurality of electron beam pass holes by etching a 0.1 to 0.25 millimeter (mm) thin plate, and molding the thin plate at a predetermined curvature. If the mask does not have a curvature equal to or greater than a predetermined level, it is permanently plastic-deformed in many cases during the manufacture of a cathode ray tube due to a decrease in the structural strength. As a result, there are many cases [[that]] in which the mask cannot perform its unique color selection function. Also, as the incidence angle of electron beams passing through the slot increases, the amount of beams passing through the slot decreases.

2. Please amend paragraph [0007] as follows:

[0007] While these recent efforts provide advantages, [[I]] we note that they fail to adequately provide an efficient and convenient manufacturing method for manufacturing an improved mask for a color cathode ray tube, and fail to adequately provide an efficient and convenient exposure mask for manufacturing the improved mask.

3. Please amend paragraph [0034] as follows:

[0034] Illustrative embodiments of the invention are described below. In the interest of clarity, not all features of an actual implementation are described. In the following description, well-known functions or constructions are not described described in detail since they would obscure the invention in unnecessary detail. It will be appreciated that, in the development of any actual embodiment, numerous implementation-specific decisions must be made to achieve the developers' specific goals, such as compliance with system-related and business-related constraints, which will vary from one implementation to another. Moreover, it will be appreciated that such a development effort might be complex and time-consuming, but would nevertheless be a routine undertaking for those of ordinary skill having the benefit of this disclosure.

4. Please amend paragraph [0051] as follows:

[0051] As shown in FIG. 17, the structure of the slots in the mask 50 and the relationship among the upper slots and the lower slots allow more of the electron beam to successfully pass through the mask 50 than other structures. As shown in FIG. 17, the structure of the slots in the mask 50 and the relationship among the upper slots and the lower slots[[,]] block less of the electron beam emitted from the electron gun 45 than other structures.

5. Please amend paragraph [0054] as follows:

[0054] The width of the bridge 56 perpendicular to the length direction of a slot is wider in the direction from the center of the mask to the periphery thereof, as shown in FIG. 18. In other words, the width W12 of a bridge 56 at a central region 100 of the mask 50 is smaller than the width W13 of a bridge 56 at a periphery region 102 of the mask 50. The bridges 56 are formed so that the widths of the bridges gradually ~~decrease~~ increase when one looks at the center of the mask and then looks across the mask over to the periphery of the mask.

6. Please amend paragraph [0058] as follows:

[0058] In the mask, the width W6 of the surface of the slot from which electron beams come out is greater than the width W5 of the surface of the slot upon which electron

beams are incident, and the center of the width W5 through which electron beams are incident is biased toward the electron beams on the center with respect to the center of the width W6. The indent 56a (Figure 7) is formed on the upper surface of the bridge 56, so that the amount of electron beams clipped while passing through the slot can be reduced. To be more specific, electron beams emitted from the electron gun 45 (Figure 4) of the cathode ray tube are deflected by the deflection yoke 47, pass through the slots formed on the holey portion 51 (Figure 6) of the mask, and land on the fluorescent film. Here, the etching boundaries of adjacent strips 55 and 55' on the mask are formed on the centers of their lateral sides, so that the aperture width between the strips 55 and 55' is maximized. The center of the inlet side of the slot is off-centered toward the center portion of the mask on the basis of the center of the outlet side of the slot, so that the amount of electron beams passing through the slot is increased to thus reduce the amount of clipping of electron beams, compared to other methods.

7. Please amend paragraph [0060] as follows:

[0060] FIG. 19 shows that an indentation 56c in a bridge at a central region of mask 50 is deeper than an indentation 56b in a bridge at a periphery of mask 50[[],] because thickness T3 is greater than thickness T4. The ~~thickness~~ thicknesses T3 and T4 are measured from the bottom surface of mask 50 to the bottom of the respective indentations.

8. Please amend paragraph [0063] as follows:

[0063] Here, the upper exposure mask 100 has an exposure pattern in which upper light transmission strips 101 are formed in parallel to each other. The upper light transmission strips 101 have widths large enough to form slots and first curved portions. Preferably, the width of each of the upper light transmission strips 101 is twice the width of each slot on the mask.

9. Please amend paragraph [0071] as follows:

[0071] While the present invention has been illustrated by the description of embodiments thereof, and while the embodiments have been described in considerable detail, it is not the intention of the applicant applicants to restrict or in any way limit the scope of the appended claims to such detail. Additional advantages and modifications will readily appear to those skilled in the art. Therefore, the invention in its broader aspects is not limited to the specific details, representative apparatus and method, and illustrative examples shown and described. Accordingly, departures may be made from such details without departing from the spirit or scope of the applicant's applicants' general inventive concept.